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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.		
10/660,565	09/12/2003	Howard Rhodes	M4065.0570/P570-A	5308		
24998	7590 04/22/2005		EXAMINER			
DICKSTEIN SHAPIRO MORIN & OSHINSKY LLP 2101 L Street, NW Washington, DC 20037			VU, QU	VU, QUANG D		
			ART UNIT	PAPER NUMBER		
			2811	-		

DATE MAILED: 04/22/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

Advisory Action Before the Filing of an Appeal Brief

Application No.	Applicant(s)
10/660,565	RHODES ET AL.
Examiner	Art Unit
Quang D. Vu	2811

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	Quang D. Vu	2811	
The MAILING DATE of this communication appe	ars on the cover sheet with the o	correspondence add	lress
THE REPLY FILED 29 March 2005 FAILS TO PLACE THIS AF	PLICATION IN CONDITION FOR A	ALLOWANCE.	
1. The reply was filed after a final rejection, but prior to or on this application, applicant must timely file one of the follow places the application in condition for allowance; (2) a Not a Request for Continued Examination (RCE) in compliant time periods:	n the same day as filing a Notice of wing replies: (1) an amendment, aff stice of Appeal (with appeal fee) in o ce with 37 CFR 1.114. The reply mo	Appeal. To avoid aba idavit, or other evider compliance with 37 C	nce, which FR 41.31; or (3)
a) \square The period for reply expires $\underline{3}$ months from the mailing date	•		
b) The period for reply expires on: (1) the mailing date of this A no event, however, will the statutory period for reply expire to	ater than SIX MONTHS from the mailing	g date of the final rejecti	on.
Examiner Note: If box 1 is checked, check either box (a) or TWO MONTHS OF THE FINAL REJECTION. See MPEP 7	06.07(f).		
Extensions of time may be obtained under 37 CFR 1.136(a). The date have been filed is the date for purposes of determining the period of exunder 37 CFR 1.17(a) is calculated from: (1) the expiration date of the set forth in (b) above, if checked. Any reply received by the Office later may reduce any earned patent term adjustment. See 37 CFR 1.704(b) NOTICE OF APPEAL	tension and the corresponding amount shortened statutory period for reply orig r than three months after the mailing da	of the fee. The appropr inally set in the final Offi	iate extension fee ice action; or (2) as
 The Notice of Appeal was filed on A brief in comp filing the Notice of Appeal (37 CFR 41.37(a)), or any exte a Notice of Appeal has been filed, any reply must be filed 	nsion thereof (37 CFR 41.37(e)), to	avoid dismissal of th	hs of the date of ne appeal. Since
AMENDMENTS	hut wis to the date of filling a brief	will not be entered b	
 The proposed amendment(s) filed after a final rejection, (a) They raise new issues that would require further co 			ecause
(b) They raise the issue of new matter (see NOTE belo		12 50.017,	
(c) They are not deemed to place the application in be appeal; and/or	•	ducing or simplifying	the issues for
(d) They present additional claims without canceling a	corresponding number of finally rej	ected claims.	
NOTE: (See 37 CFR 1.116 and 41.33(a)).	-		
4. The amendments are not in compliance with 37 CFR 1.1	21. See attached Notice of Non-Co	mpliant Amendment	(PTOL-324).
5. Applicant's reply has overcome the following rejection(s)			
 Newly proposed or amended claim(s) would be a non-allowable claim(s). 	llowable if submitted in a separate,	timely filed amendme	ent canceling the
7. For purposes of appeal, the proposed amendment(s): a) how the new or amended claims would be rejected is pro The status of the claim(s) is (or will be) as follows: Claim(s) allowed: Claim(s) objected to: Claim(s) rejected: 90 and 93-141. Claim(s) withdrawn from consideration:		Il be entered and an o	explanation of
AFFIDAVIT OR OTHER EVIDENCE			
8. The affidavit or other evidence filed after a final action, but because applicant failed to provide a showing of good an was not earlier presented. See 37 CFR 1.116(e).	ut before or on the date of filing a N id sufficient reasons why the affidat	otice of Appeal will <u>ne</u> vit or other evidence i	ot be entered s necessary and
 The affidavit or other evidence filed after the date of filing entered because the affidavit or other evidence failed to showing a good and sufficient reasons why it is necessar 	overcome <u>all</u> rejections under appe y and was not earlier presented. S	al and/or appellant fa See 37 CFR 41.33(d)(ils to provide a 1).
 The affidavit or other evidence is entered. An explanation REQUEST FOR RECONSIDERATION/OTHER 	on of the status of the claims after e	ntry is below or attac	hed.
 The request for reconsideration has been considered by See Continuation Sheet. 	ut does NOT place the application i	n condition for allowa	nce because:
12. Note the attached Information Disclosure Statement(s).	(PTO/SB/08 or PTO-1449) Paper N	Vo(s)	
13. Other:		1.W'	
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TECHNOLOGY CENTER 2800

Continuation of 11. does NOT place the application in condition for allowance because: It is argued, in page 3 of the remarks, that Rhodes does not teach or suggest forming a floating diffusion region for receiving charge from the charge collection region; and forming a charge storage capacitor over the semiconductor substrate so that one electrode of the storage capacitor is connected to the floating diffusion region by an electrical contact. This argument is not convincing because Rhodes (figures 1-14) teaches forming a floating diffusion region (130) for receiving charge from the charge collection region (155) (Rhodes teaches doped region [126], which is connected photogate transistor [125] to the transfer transistor gate [128]; [155] is a part of the transistor [125] and [130] is a part of the transistor [128]. So, [155] is connected to the [130]. Therefore, a floating diffusion region [130] receives charge from the charge collection region [155]); and forming a charge storage capacitor (162) over the semiconductor substrate (116, 120) so that one electrode (156) of the storage capacitor (162) is connected to the floating diffusion region (130) by an electrical contact (150).

It is argued, in page 3 of the remarks, that Rhodes and Doyle et al. do not teach or suggest the trench and planar capacitor structures that are all formed overlying the active area of the pixel sensor cell, and not such that the entire extent of the charge storage capacitor overlies the field oxide region. This argument is not convincing because the applicant fails to define the trench and planar capacitor structures that are all formed overlying the active area of the pixel sensor cell in the claimed limitations of claim 130. However, the combined device (Rhodes and Doyle et al.) includes forming a charge storage capacitor (Doyle et al.; C2) such that the entire extent of the charge storage capacitor (Doyle et al.; C2) overlies the field oxide region (Doyle et al.; 40) for the reason that is discussed in the final office.

It is argued, in page 4 of the remarks, that Rhodes does not teach or suggest connecting an electrode of a storage capacitor to a floating diffusion region by a first electrical contact. This argument is not convincing because the applicant fails to define connecting an electrode of a storage capacitor to a floating diffusion region by a first electrical contact in the claimed limitations of claim 137. However, Rhodes (figures 1-14) includes connecting an electrode of a first charge storage capacitor (capacitors [64, 74]; figure 1) to the floating diffusion region (130) by a first electrical contact (42) (floating diffusion region [130] connects to a readout circuit [60]; column 7, lines 42-54).

It is argued, in page 6 of the remarks, that Rhodes and Doyle et al. do not teach or suggest forming a charge storage capacitor such that the entire extent of the charge storage capacitor overlies the field oxide region and forming a contact between the first doped region and the charge storage capacitor. This argument is not convincing because the combined device (Rhodes and Doyle et al.) includes forming a contact (Rhodes; 150) between the first doped region (Rhodes; 155) and the charge storage capacitor (Rhodes; 162) and forming a charge storage capacitor (Doyle et al.; C2) such that the entire extent of the charge storage capacitor (Doyle et al.; C2) overlies the field oxide region (Doyle et al.; 40) for the reason that is discussed in the final office.